

## EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	19	(capacitor same trench) and aberrat\$3 and pattern	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/06 08:04
L2	21	(capacitor same trench) and aberrat\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/06 08:07
L3	1370	capacitor and aberrat\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/06 08:08
L4	61	capacitor same aberrat\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/06 08:08
L5	7	capacitor same aberrat\$3 and trench	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/06 10:29
L6	305	(capacitor with trench) same (test\$3 or examin\$3 or evaluat\$3 or estimat\$3 or check\$3 or verif\$3 or monitor\$3 or assessment or analyz\$3 or analysis)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/06 08:40
L7	3	(capacitor with trench) same (test\$3 or examin\$3 or evaluat\$3 or estimat\$3 or check\$3 or verif\$3 or monitor\$3 or assessment or analyz\$3 or analysis) and aberrat\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/06 09:40
L8	2	(capacitor with trench) same (test\$3 or examin\$3 or evaluat\$3 or estimat\$3 or check\$3 or verif\$3 or monitor\$3 or assessment or analyz\$3 or analysis) and aberrat\$3 and (pattern same layout)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/06 09:41
L9	3	(capacit\$4 with trench) same (test\$3 or examin\$3 or evaluat\$3 or estimat\$3 or check\$3 or verif\$3 or monitor\$3 or assessment or analyz\$3 or analysis) and aberrat\$3 and (pattern same layout)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/06 09:41

## EAST Search History

L10	3	(capacit\$4 same trench) same (test\$3 or examin\$3 or evaluat\$3 or estimat\$3 or check\$3 or verif\$3 or monitor\$3 or assessment or analyz\$3 or analysis) and aberrat\$3 and (pattern same layout)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/06 10:26
L11	13	(trench or DT) same (test\$3 or examin\$3 or evaluat\$3 or estimat\$3 or check\$3 or verif\$3 or monitor\$3 or assessment or analyz\$3 or analysis) and aberrat\$3 and (pattern same layout)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/06 09:46
L12	9	(trench or DT) same (test\$3 or examin\$3 or evaluat\$3 or estimat\$3 or check\$3 or verif\$3 or monitor\$3 or assessment or analyz\$3 or analysis) and aberrat\$3 and (pattern same layout same (shape or H))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/06 09:47
L13	9	(trench or DT) same (test\$3 or examin\$3 or evaluat\$3 or estimat\$3 or check\$3 or verif\$3 or monitor\$3 or assessment or analyz\$3 or analysis) and aberrat\$3 and (pattern same layout same (shape or "H"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/06 09:54
L14	5	(capacitor with (deep adj trench) or DT or trench) same layout same "H" and aberrat\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/06 10:22
L15	5	(capacitor with (deep adj trench) or DT or trench) same layout same "H" and (aberrat\$4 or unsymmetr\$4 or assymetr\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/06 10:23
L16	5	(capacitor with (deep adj trench) or DT or trench) same layout same "H" and (aberrat\$4 or unsymmetr\$4 or asymetr\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/06 10:25
L17	3	(capacit\$4 same trench) same (test\$3 or examin\$3 or evaluat\$3 or estimat\$3 or check\$3 or verif\$3 or monitor\$3 or assessment or analyz\$3 or analysis) and (aberrat\$4 or unsymmetr\$4 or asymetr\$4) and (pattern same layout)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/06 10:26
L18	15	capacitor same (aberrat\$4 or unsymmetr\$4 or asymetr\$4) and trench	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/06 10:29

## EAST Search History

L21	6	(capacitor same trench) and (aberrat\$4 or unsymmetr\$4 or asymetr\$4) and (pattern same test)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/06 13:46
L22	19	(capacitor same trench) and (pattern same test same (length or width or distance))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/06 13:48
L23	9	(capacitor same trench) and (pattern same test same (length or width or distance)) and (photomask or photolithography)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/06 13:48
L24	14	(capacitor same trench) and (pattern same test same (length or width or distance)) and (photomask or photolithography or lithography)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/06 15:10
L25	152	((capacitor same trench) same (layout or pattern) same (distance or length or width)) and (photomask or photolithography or lithography)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/06 15:11
L26	83	((capacitor same trench) same (layout or pattern) same (distance or length or width)) same (photomask or photolithography or lithography or mask)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/06 15:11
L27	69	((capacitor with trench) same (layout or pattern) same (distance or length or width)) same (photomask or photolithography or lithography or mask)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/06 15:21
L28	3	((capacitor with trench) same (layout or pattern) same (distance or length or width) same pair) same (photomask or photolithography or lithography or mask)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/06 15:33
L29	13	((capacitor with trench) same (layout or pattern) same (distance or length or width) same pair) and (photomask or photolithography or lithography or mask)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/06 15:33
S1	23	(lens near3 aberration near3 effect) and "716"/\$.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/05 15:21

## EAST Search History

S2	5	(lens near3 aberration near3 effect) and (test with pattern) and "716"/\$.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/05 15:27
S3	2	"20050229147"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/05 15:25
S4	1	(lens near3 aberration near3 effect) and (test same pattern) and ((deep adj2 trench) same capacit\$4) and "716"/\$.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/05 15:29
S5	1	(lens near3 aberration near3 effect) and test and ((deep adj2 trench) same capacit\$4) and "716"/\$.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/05 15:29
S6	1	(lens near3 aberration near3 effect) and (test\$3 or verif\$3 or check\$3 or monitor\$3 or analysis or analyz\$3 or estimat\$3 or evaluat\$3 or assessment or examin\$3) and (((deep adj2 trench) or DT) same capacit\$4) and "716"/\$.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/05 15:44
S7	1	(fabricat\$3 same (capacitor with (DT or (deep adj2 trench)))) and aberrat\$3 and COMA and ((S3 or three) adj foil)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/05 15:46
S8	1	(fabricat\$3 same capacitor same trench) and aberrat\$3 and COMA and ((S3 or three) adj foil)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/05 15:46
S9	1	(fabricat\$3 same capacitor same trench) and aberrat\$3 and ((S3 or three) adj foil)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/05 15:47
S10	8	(fabricat\$3 same capacitor same trench) and aberrat\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/05 16:01

## EAST Search History

S11	15	((fabricat\$3 or manufactur\$3) same capacitor same trench) and aberrat\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/05 16:18
S12	13	((fabricat\$3 or manufactur\$3) same capacitor same trench) and aberrat\$3 and pattern	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/05 16:02
S13	1	"6163376".PN.	USPAT; USOCR	OR	ON	2006/06/05 16:16
S14	2	((fabricat\$3 or manufactur\$3) same capacitor same trench) and aberrat\$3 and (test near3 area)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/05 16:19
S15	2	((fabricat\$3 or manufactur\$3) same capacitor same trench) and aberrat\$3 and ((test near3 area) with layout)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/05 16:20
S16	13	((fabricat\$3 or manufactur\$3) same capacitor same trench) and aberrat\$3 and pattern	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/06 10:34

[Home](#) | [Login](#) | [Logout](#) | [Access Inform](#)


Welcome United States Patent and Trademark Office

## Search Results

[BROWSE](#)   [SEARCH](#)   [IEEE XPLORE GUIDE](#)

Results for "((deep and trench and capacitor and (test\* or verif\* or examin\* or estim\* or evaluat\* or check\*)) and...")

Your search matched 2 of 1351636 documents.

A maximum of 100 results are displayed, 25 to a page, sorted by **Relevance** in **Descending** order.

### » Search Options

[View Session History](#)

[New Search](#)

### » Key

**IEEE JNL** IEEE Journal or Magazine

**IEE JNL** IEE Journal or Magazine

**IEEE CNF** IEEE Conference Proceeding

**IEE CNF** IEE Conference Proceeding

**IEEE STD** IEEE Standard

### Modify Search

((deep and trench and capacitor and (test\* or verif\* or examin\* or estim\* or evaluat\* or check\*)) and...")

Check to search only within this results set

**Display Format:**  Citation  Citation & Abstract

[view selected items](#)

[Select All](#) [Deselect](#)

All

- 1. A highly cost efficient 8F<sup>2</sup> DRAM cell with a double transistor device for 100 nm and beyond  
Weis, R.; Hummler, K.; Akatsu, H.; Kudelka, S.; Dyer, Scholz, A.; Kim, B.; Wise, M.; Malik, R.; Strane, J.; Gc McStay, K.; Beintner, J.; Arnold, N.; Gerber, R.; Liegl, Economikos, L.; Simpson, A.; Yan, W.; Dobuzinsky, C; Nesbit, L.; Radens, C.J.; Divakaruni, R.; Bergner, W.; Mueller, W.; [Electron Devices Meeting, 2001. IEDM Technical Digest](#) 2-5 Dec. 2001 Page(s):18.7.1 - 18.7.4 Digital Object Identifier 10.1109/IEDM.2001.979525 AbstractPlus | Full Text: [PDF\(323 KB\)](#) IEEE CNF Rights and Permissions
  
- 2. Wafer current measurement for process monitoring  
Shur, D.; Kadyshevitch, A.; Zelenko, J.; Duncan, C.; Ventola, S.; Klinger, J.; [Advanced Semiconductor Manufacturing, 2004. ASMC Conference and Workshop](#) 4-6 May 2004 Page(s):303 - 307 Digital Object Identifier 10.1109/ASMC.2004.1309586 AbstractPlus | Full Text: [PDF\(414 KB\)](#) IEEE CNF Rights and Permissions

[Help](#) [Content](#)  
[Search](#)

© Copyright